## IN THE CLAIMS

1. (Currently Amended) A processing apparatus comprising:

a holding member which holds and rotates [said] a target;

a first nozzle which supplies a first process solution to an edge portion

of one surface of said target in a state that said holding member is holding and

rotating said target;

a second nozzle which supplies a second process solution to the edge

portion of one surface of said target, to which surface while said first nozzle is

supplying supplies said first process solution to said one surface of said target; and

a sucking hole provided in the vicinity of the edge portion of said

target, which sucks a discharge solution of said first process solution and said

second process solution.

2. (Currently Amended) The processing apparatus according to claim 1,

wherein said second nozzle supplies said second process solution to a downstream

side position in the rotational direction of said target from relative to a position to

which said first nozzle supplies said first process solution.

3. (Currently Amended) The processing apparatus according to claim 1,

wherein said second nozzle supplies said second process solution to a an outer

position at a greater radial distance from the center of said target than a position to

which said first nozzle supplies said first process solution.

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4. (Original) The processing apparatus according to claim 1, wherein said

first nozzle and said second nozzle are provided at an angle of 0° to 90° with respect

to one surface of said target.

5. (Original) The processing apparatus according to claim 1, wherein said

first nozzle and said second nozzle are provided in the vicinity of both surfaces of

said target.

6. (Currently Amended) The processing apparatus according to claim 1,

wherein a plurality of each of said first nozzle, said second nozzle and said sucking

hole [is] are provided around said target.

7. (Original) The processing apparatus according to claim 1, wherein said

first nozzle, said second nozzle and said sucking hole are integrated, and are

movable back and forth in the vicinity of the edge portion of said target at the time

of processing said target.

8. (Currently Amended) A processing apparatus comprising:

a holding member which holds and rotates [[said]] a target;

a supply nozzle provided at one surface side of said target, which

supplies a process solution to the one surface of said target; and

a blocking member provided in the other surface side of said target,

which blocks the process solution which flows from the one surface to the other

surface of said target to provide a given processing to an edge portion of the other

surface.

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9. (Original) The processing apparatus according to claim 8, wherein said blocking member is provided in the vicinity of the edge portion of the other surface of said target.

10. (Original) The processing apparatus according to claim 8, wherein said blocking member injects fluid to the edge portion of the other surface of said target.

11 - 15. (Canceled)

16. (Currently Amended) The processing apparatus according to claim

15, A processing apparatus comprising:

a holding member which holds and rotates a target;

a first nozzle which supplies a first process solution to a central portion of a surface of said target in a state that said holding member is holding and rotating said target;

a second nozzle which supplies a second process solution to an edge portion of the surface of said target while said first nozzle is supplying said first process solution to said one surface of said target; and

a third nozzle having: a plurality of pipes radially provided on the same plane and through which a process solution flows; and a plurality of holes in each of said pipes, provided at the side opposite to one surface of said target, through which said process solution is supplied to the surface of said target;

wherein the diameter of each of said hole is increased said holes increases from one end of each said pipe to the other end of each said pipe.

17. (Currently Amended) A processing system including:

a transfer device which transfers a target; and

a processing apparatus which provides predetermined processing to

said target transferred to said processing apparatus by said transferring device;

said processing [device] apparatus comprising:

a holding member which holds and rotates said target;

a first nozzle which supplies a first process solution to an edge portion

of one surface of said target in a state that said holding member is holding and

rotating said target;

a second nozzle which supplies a second process solution to the edge

portion of one surface of said target, to which surface while said first nozzle is

supplying supplies said first process solution to said one surface of said target; and

a sucking hole provided in the vicinity of the edge portion of said

target, which sucks a discharge solution of said first process solution and said

second process solution.

18. (Currently Amended) The processing system according to claim 17,

wherein said second nozzle supplies said second process solution to a downstream

position in the rotational direction of said target from relative to a position to which

said first nozzle supplies said first process solution.

19. (Original) The processing system according to claim 17, wherein said

second nozzle supplies said second process solution to a an outer position at a

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greater radial distance from the center of said target than a position to which said first nozzle supplies said first process solution.

- 20. (Original) The processing system according to claim 17, wherein said first nozzle and said second nozzle are provided at an angle of 0° to 90° with respect to one surface of said target.
- 21. (Original) The processing system according to claim 17, wherein said first nozzle and said second nozzle are provided in the vicinity of both surfaces of said target.
- 22. (Currently Amended) The processing system according to claim 17, wherein a plurality of each of said first nozzle, said second nozzle and said sucking hole [is] are provided around said target.
- 23. (Original) The processing system according to claim 17, wherein said first nozzle, said second nozzle and said sucking hole are integrated, and are movable back and forth in the vicinity of the edge portion of said target at the time of processing said target.
  - 24. (Currently Amended) A processing system including:
    - a transfer device which transfers a target; and
- a processing apparatus which provides predetermined processing to said target transferred to said processing apparatus by said transferring device;
  - said processing device apparatus comprising:
  - a holding member which holds and rotates said target;

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a supply nozzle provided at one surface side of said target, which supplies a process solution to the one surface of said target; and

a blocking member provided at the other surface side of said target, which blocks the process solution which flows from the one surface to the other surface of said target to provide a given processing to an edge portion of the other surface.

25. (Original) The processing system according to claim 24, wherein said blocking member is provided in the vicinity of the edge portion of said other surface of said target.

26. (Original) The processing system according to claim 24, wherein said blocking member injects fluid to the edge portion of said other surface of said target.

27 - 31. (Canceled)

32. (Currently Amended) The processing system according to claim-31, A processing system including:

a transfer device which transfers a target; and

a processing apparatus which provides predetermined processing to the target transferred to said processing apparatus by said transferring device;

said processing device comprising:

a holding member which holds and rotates said target;

a first nozzle which supplies a first process solution to a central portion of a surface of said target in a state that said holding member is holding and rotating said target;

a second nozzle which supplies a second process solution to an edge portion of the surface of said target while said first nozzle is supplying said first process solution to said one surface of said target; and

a third nozzle having a plurality of pipes radially provided on the same plane and through which a process solution flows; and a plurality of holes in each of said pipes, provided at the side opposite to one surface of said target, through which said process solution is supplied to the surface of said target,

wherein the diameter of each of said hole is increased said holes increases from one end of each said pipe to the other end of each said pipe.

33. (Currently Amended) A processing method comprising the steps of:

supplying a first process solution to one edge portion of a target in a state that said target is rotating;

supplying a second process solution to <u>a</u> downstream <u>position relative</u> to from a position to which said first process solution is supplied, <u>wherein said</u> second process solution is supplied to said downstream <u>position while</u> said first nozzle <u>is supplying supplies</u> said first process solution <u>to the edge portion of said</u> target; and

sucking atmosphere in the vicinity of the edge portion of said target to which said first and second process solutions are supplied.

34. (Canceled)

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35. (New) The processing apparatus according to claim 1, wherein said first

process solution and said second process solution comprise different types of process

solutions.

36. (New) The processing apparatus according to claim 1, wherein said first

process solution comprises hydrogen peroxide and said second process solution

comprises hydrofluoric acid.

37. (New) The processing system according to claim 17, wherein said first

process solution and said second process solution comprise different types of process

solutions.

38. (New) The processing method according to claim 33, wherein said first

process solution and said second process solution comprise different types of process

solutions.